Data & Configuration

Description: Diffusion（ Amorphous Anneal ，α-Si ）
Manufacturer: TEL
Model: FORMULA
Wafer Size: 300mm
Vintage: 2009.
S/W Version 2.0

Configuration:
< Basic Configuration >
Thoroughput: 50 wafers in Batch

Temperature: 850℃

Gas Unit: PH3 1% ,F2, H2, O2 ,
System Controller: WAVES/Model780
Heater: Mid-Temp VCM-50-XXX
Exhaust Controller: CKD VEC
EXH Box: Standard Type (190 cm width)
Dry Pump: Exclude

< Gas Configuration >

Gas	Pressure	Flow	Connection Type
Gas Box			
P-N2	0.5MPa	92 L/min	ϕ1/4"UJR
1%PH3/He	0.2MPa	5 L/min	ϕ1/4"UJR
H2	0.2MPa	5 L/min	ϕ1/4"UJR
O2	0.2MPa	5 L/min	ϕ1/4"UJR
F2	0.2MPa	5 L/min	ϕ1/4"UJR
EXH Box			
P-N2	-	-	ϕ3/4"SWG
P-N2	-	-	ϕ1/2"SWG
P-N2	-	-	ϕ1/2"SWG
D-N2	-	-	ϕ3/8"SWG

D-N2 - - ϕ3/8"SWG

D-N2 - - ϕ1/4"SWG

Vacuum 20KPa - ϕ3/8"SWG

RCU

P-N2 0.7MPa 1200 L/Min ϕ3/4"SWG

D-N2 0.7MPa - ϕ1/4"SWG

P-N2 - - ϕ3/4"SWG

P-N2 - - ϕ1/2"SWG

P-N2 - - ϕ1/2"SWG

D-N2 - - ϕ3/8"SWG

D-N2 - - ϕ3/8"SWG

D-N2 - - ϕ1/4"SWG

Pump

D-N2 0.7MPa - ϕ1/4"SWG

D-N2 0.7MPa 110 L/min ϕ1/2"SWG